

WHAT IS CLAIMED IS:

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7. A scanning exposure apparatus for transferring a pattern of a master onto each shot region while synchronously scanning the master and a substrate on which a plurality of shot regions are arrayed, comprising:

a master stage for moving the master;

a substrate stage for moving the substrate; and

a controller for controlling movement of said

10 substrate stage over a plurality of shot regions so as to assure a setting distance serving as a distance for scanning and moving said substrate stage at a uniform velocity in order to guarantee that synchronization error between said master stage and said substrate  
15 stage falls within an allowable range after said substrate stage is accelerated up to a scan speed for scanning exposure,

wherein said controller controls the movement of said substrate stage such that a setting distance for a  
20 first shot region to be scanned and exposed upon a change in row to which a shot region of an exposure object belongs is set longer than a setting distance for other shot regions.

2. The apparatus according to claim 1, wherein said  
25 controller controls the continuous movement of said substrate stage in accordance with a common setting distance for shot regions other than the first shot

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region to be scanned and exposed among a plurality of shot regions belonging to one row.

3. The apparatus according to claim 1, wherein said controller controls the continuous movement of said  
5 substrate stage in accordance with a setting distance determined for each row to which a plurality of shot regions belong.

4. The apparatus according to claim 1, wherein the setting distance is determined on the basis of a  
10 setting time until synchronization error between said master stage and said substrate stage falls within an allowable range after said substrate stage is accelerated up to a scan speed for scanning exposure.

5. A scanning exposure apparatus for transferring a  
15 pattern of a master onto each shot region while synchronously scanning the master and a substrate on which a plurality of shot regions are arrayed, comprising:

a master stage for moving the master;  
20 a substrate stage for moving the substrate; and  
a controller for controlling movement of said substrate stage for a plurality of shot regions so as to assure a setting distance serving as a distance for scanning and moving said substrate stage at a uniform  
25 velocity in order to guarantee that synchronization error between said master stage and said substrate stage falls within an allowable range after said

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substrate stage is accelerated up to a scan speed for scanning exposure,

wherein said controller controls movement of said substrate stage in accordance with a setting distance  
5 determined for each row to which a plurality of shot regions belong.

6. The apparatus according to claim 5, wherein the setting distance is determined on the basis of a setting time until synchronization error between said  
10 master stage and said substrate stage falls within an allowable range after said substrate stage is accelerated up to a scan speed for scanning exposure.

7. A scanning exposure method of transferring a pattern of a master onto each shot region while  
15 synchronously scanning the master and a substrate on which a plurality of shot regions are arrayed, comprising:

the control step of controlling movement of a substrate stage for a plurality of shot regions so as  
20 to assure a setting distance serving as a distance for scanning and moving the substrate stage at a uniform velocity in order to guarantee that synchronization error between a master stage and the substrate stage falls within an allowable range after the substrate  
25 stage is accelerated up to a scan speed for scanning exposure,

wherein in the control step, the movement of the

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substrate stage is controlled such that a setting distance for a first shot region to be scanned and exposed upon a change in row to which a shot region of an exposure object belongs is set longer than a setting distance for other shot regions.

8. The method according to claim 7, wherein in the control step, the continuous movement of said substrate stage is controlled in accordance with a common setting distance for shot regions other than the first shot region to be scanned and exposed among a plurality of shot regions belonging to one row.

9. The method according to claim 7, wherein in the control step, the continuous movement of said substrate stage is controlled in accordance with a setting distance determined for each row to which a plurality of shot regions belong.

10. The method according to claim 7, wherein the setting distance is determined on the basis of a setting time until synchronization error between the master stage and the substrate stage falls within an allowable range after the substrate stage is accelerated up to a scan speed for scanning exposure.

11. A scanning exposure method of transferring a pattern of a master onto each shot region while synchronously scanning the master and a substrate on which a plurality of shot regions are arrayed, comprising:

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the control step of controlling movement of a substrate stage for a plurality of shot regions so as to assure a setting distance serving as a distance for scanning and moving the substrate stage at a uniform velocity in order to guarantee that synchronization error between a master stage and the substrate stage falls within an allowable range after said substrate stage is accelerated up to a scan speed for scanning exposure,

10 wherein in the control step, movement of the substrate stage is controlled in accordance with a setting distance determined for each row to which a plurality of shot regions belong.

12. The method according to claim 11, wherein the setting distance is determined on the basis of a setting time until synchronization error between the master stage and the substrate stage falls within an allowable range after said substrate stage is accelerated up to a scan speed for scanning exposure.

20 13. A semiconductor device manufacturing method comprising the steps of:

installing manufacturing apparatuses for various processes including the scanning exposure apparatus defined in claim 1 in a semiconductor manufacturing factory; and

manufacturing a semiconductor device in a plurality of processes by using the manufacturing

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apparatuses.

14. The method according to claim 13, further comprising the steps of:

connecting the manufacturing apparatuses by a  
5 local area network; and  
communicating information about at least one of  
the manufacturing apparatuses between the local area  
network and an external network of the semiconductor  
manufacturing factory.

10 15. The method according to claim 13, further comprising the step of acquiring maintenance information of the scanning exposure apparatus by accessing a database provided by a vendor or user of the scanning exposure apparatus via the external  
15 network.

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16. A semiconductor manufacturing factory comprising:  
manufacturing apparatuses for various processes  
including the scanning exposure apparatus defined in  
claim 1;

20 a local area network for connecting said manufacturing apparatuses; and  
a gateway for allowing the local area network to access an external network of the factory,  
wherein information about at least one of said  
25 manufacturing apparatuses is communicated.

17. A maintenance method for the scanning exposure apparatus defined in claim 1 that is installed in a



external network.

20. A semiconductor device manufacturing method comprising the steps of:

installing manufacturing apparatuses for various processes including the scanning exposure apparatus defined in claim 5 in a semiconductor manufacturing factory; and

manufacturing a semiconductor device in a plurality of processes by using the manufacturing apparatuses.

21. The method according to claim 20, further comprising the steps of:

connecting the manufacturing apparatuses by a local area network; and

communicating information about at least one of the manufacturing apparatuses between the local area network and an external network of the semiconductor manufacturing factory.

22. The method according to claim 21, further comprising the step of acquiring maintenance information of the scanning exposure apparatus by accessing a database provided by a vendor or user of the scanning exposure apparatus via the external network.

23. A semiconductor manufacturing factory comprising: manufacturing apparatuses for various processes including the scanning exposure apparatus defined in

claim 5;

a local area network for connecting said  
manufacturing apparatuses; and

a gateway for allowing the local area network to  
5 access an external network of the factory,

wherein information about at least one of said  
manufacturing apparatuses is communicated.

24. A maintenance method for the scanning exposure  
apparatus defined in claim 5 that is installed in a  
10 semiconductor manufacturing factory, comprising the  
steps of:

causing a vendor or user of the scanning exposure  
apparatus to provide a maintenance database connected  
to an external network of the semiconductor  
15 manufacturing factory;

authenticating access from the semiconductor  
manufacturing factory to the maintenance database via  
the external network; and

transmitting maintenance information accumulated  
20 in the maintenance database to the semiconductor  
manufacturing factory via the external network.

25. The apparatus according to claim 5, further  
comprising:

a display;  
25 a network interface; and  
a computer for executing network software,  
wherein maintenance information of the scanning

